

# EUROPEAN PATENT OFFICE

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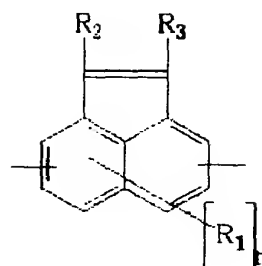
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TITLE : ANTIREFLECTION FILM FORMING  
COMPOSITION



ABSTRACT : PROBLEM TO BE SOLVED: To obtain the subject composition capable of forming a resist pattern having a high antireflection effect, not causing an inter mixing, having excellent resolution, accuracy, etc. by including a polymer containing a bifunctional group shown by a specific chemical structure and a solvent.

SOLUTION: This composition comprises a polymer containing a bifunctional group of the formula (R1 is a monovalent atom or a monofunctional group; n is 0-4; plural R1 groups may be the same or different when n is 2-4; R2 and R3 are each a monovalent atom or a monofunctional group), a solvent such as ethylene glycol monomethyl ether, etc., (the amount of the solvent mixed is an amount to make the solid concentration of the obtained composition 0.1-50 wt.%) and preferably a curing agent such as tolylene diisocyanate, etc. The polymer is obtained, for example, by a condensation reaction between an acenaphthylene and an aldehyde.

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